

Amendments to the Abstract:

Kindly amend the Abstract, as follows:

Material A method and apparatus for depositing material on a substrate is provided in which material (4) is deposited on a substrate (8) by arranging the material in a container (2), and contacting the surface of the material (4) with a beam of electrons to so as to evaporate the material and transfer it to the substrate. A shield (7) opaque to electrons is arranged to cover a portion of the surface contacted by the beam of electrons. Relative movement occurs between the container (2) on one hand and the shield (7) and the beam of electrons on the other hand such that the portion of the surface previously contacted by the beam of electrons is no longer covered by the shield and is exposed to the substrate (8).